

Fig. 1A

10

11

12

13

Fig. 18

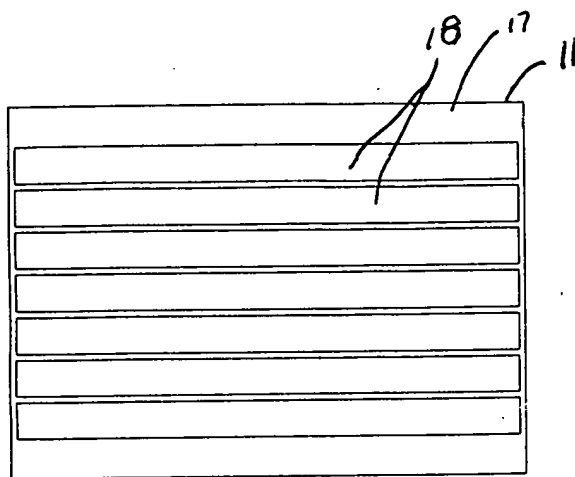


Fig. 2A

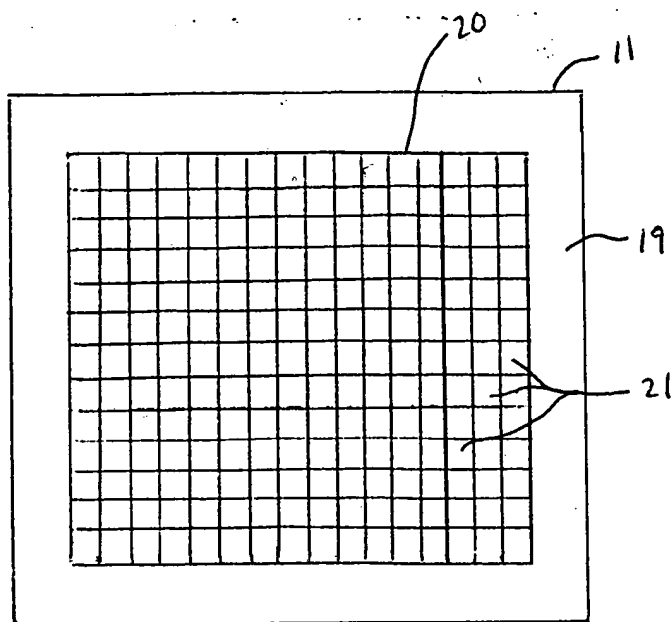


Fig. 2B

Downloaded from www.ascelibrary.org

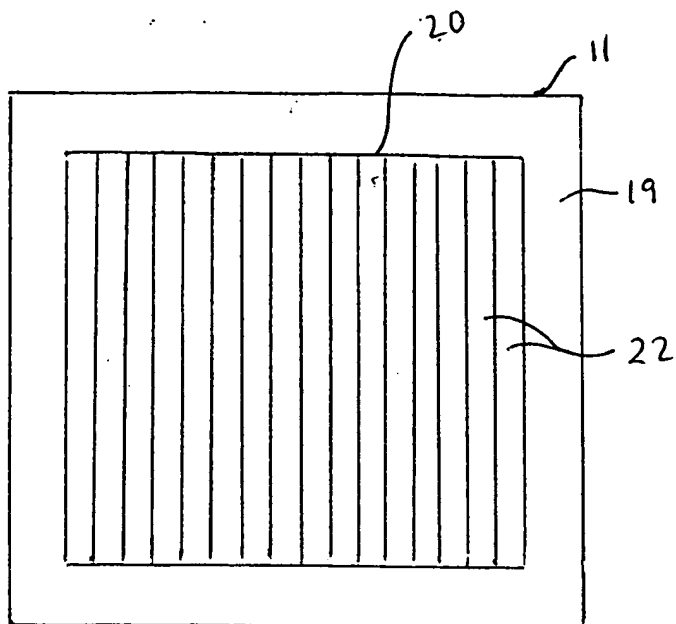


Fig. 2C

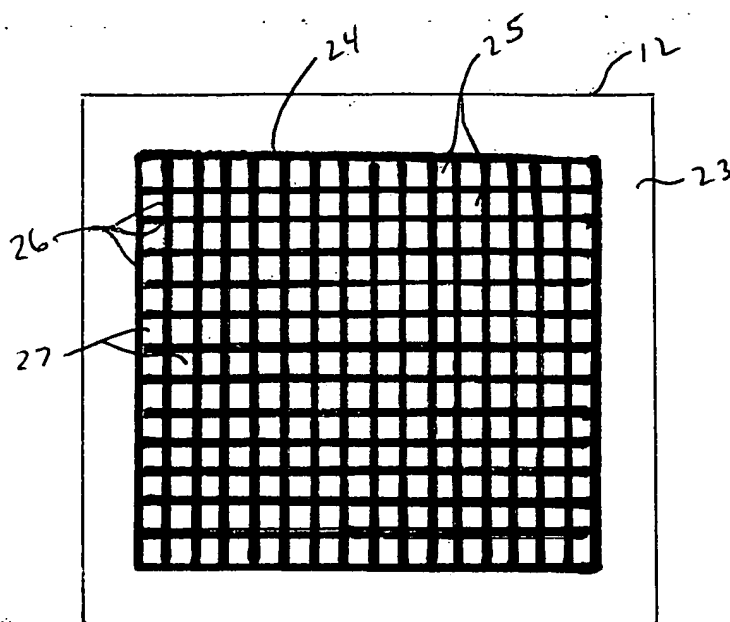


Fig. 3A

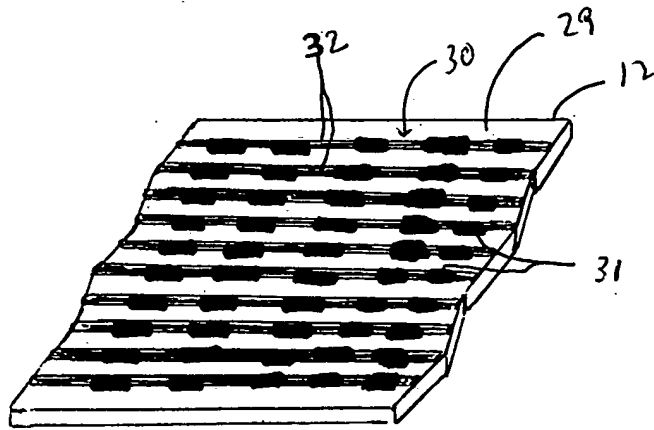


Fig. 3B

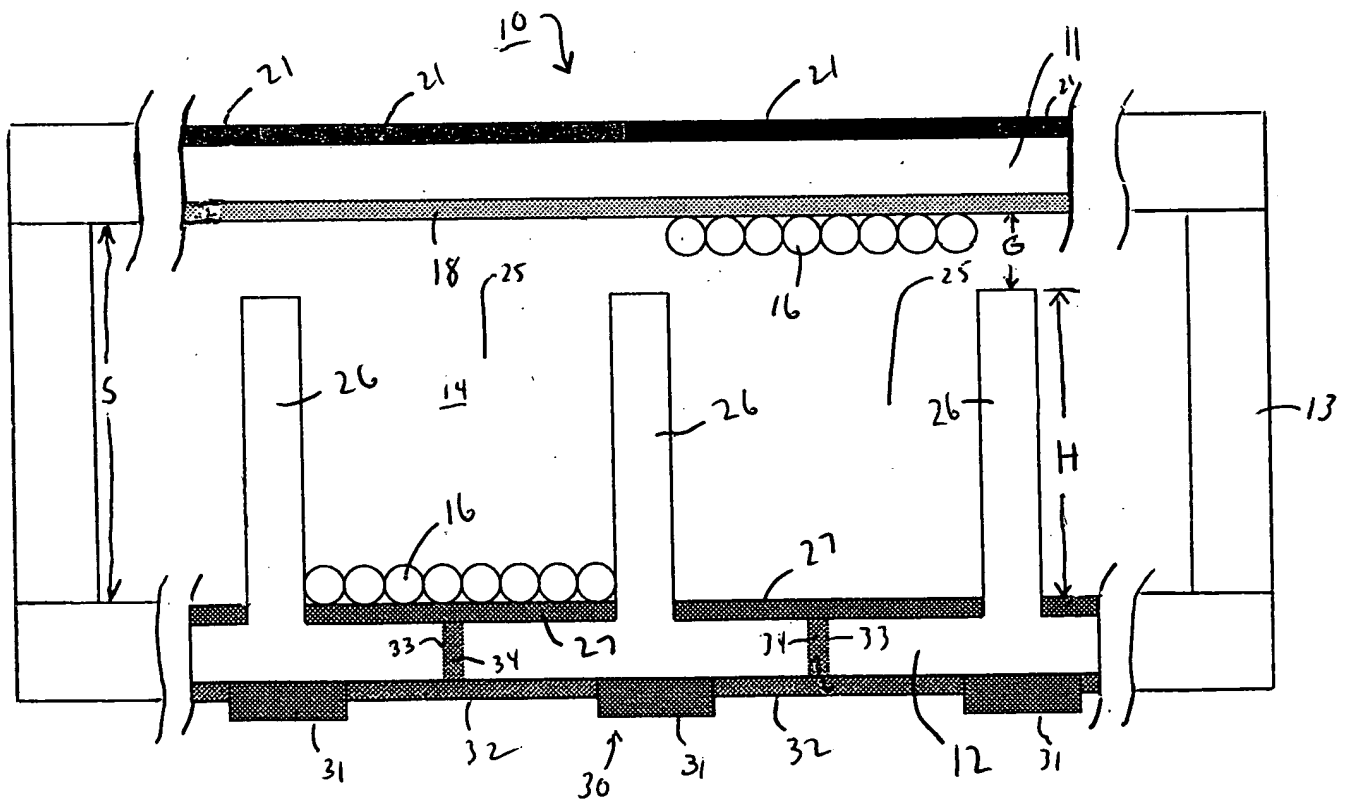


Fig. 4

This diagram shows a cross-sectional view of a photolithography mask assembly. It consists of a substrate (12) with a photoresist layer (14) on top. The photoresist layer is divided into rectangular regions (16) by vertical spacers (26). The regions (16) are filled with a material (25). The spacers (26) are also filled with the same material (25). The top surface of the photoresist layer is labeled 'Dark' in four locations, indicating it is not exposed to light. The entire assembly is covered by a thin layer (21) and a top layer (22).

Fig. 5A

A cross-sectional view of a color filter assembly. It shows a substrate 12 with a series of vertical pillars 26. On top of the pillars, there are circular elements 16. A layer 14 is formed on top of the pillars and the substrate. Above the layer 14, there is a thin layer 21. Arrows indicate light rays passing through the layer 21 and hitting the circular elements 16. The light rays are labeled: Red, Dark (Green), Blue, and Red. The label 21 is also present near the top of the pillars.

Fig. 5B

[illegible]

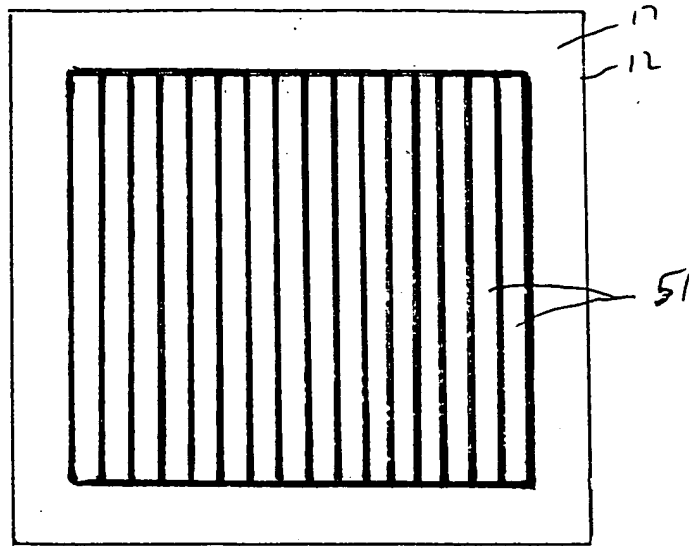


Fig. 6

702

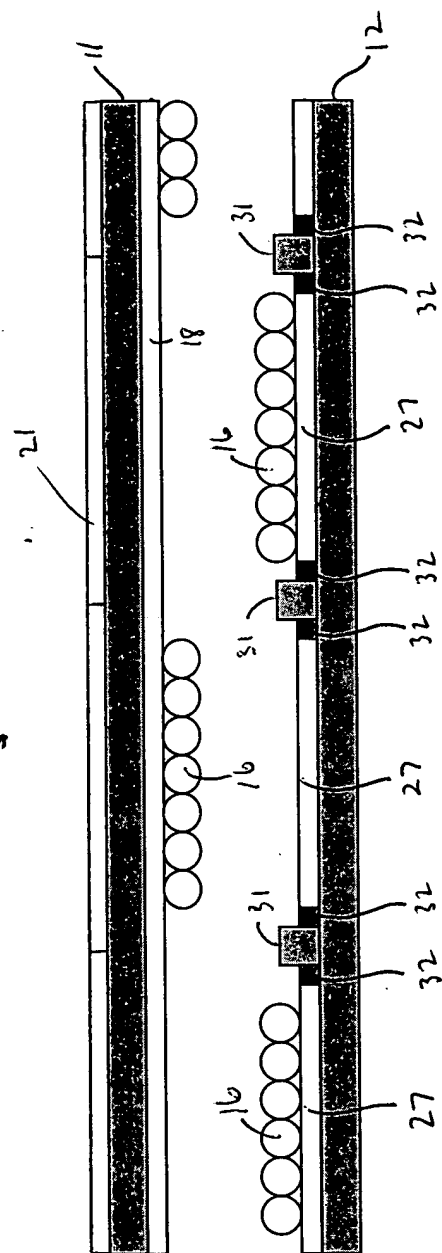


Fig. 7A



Fig. 7B

COILED SECTION

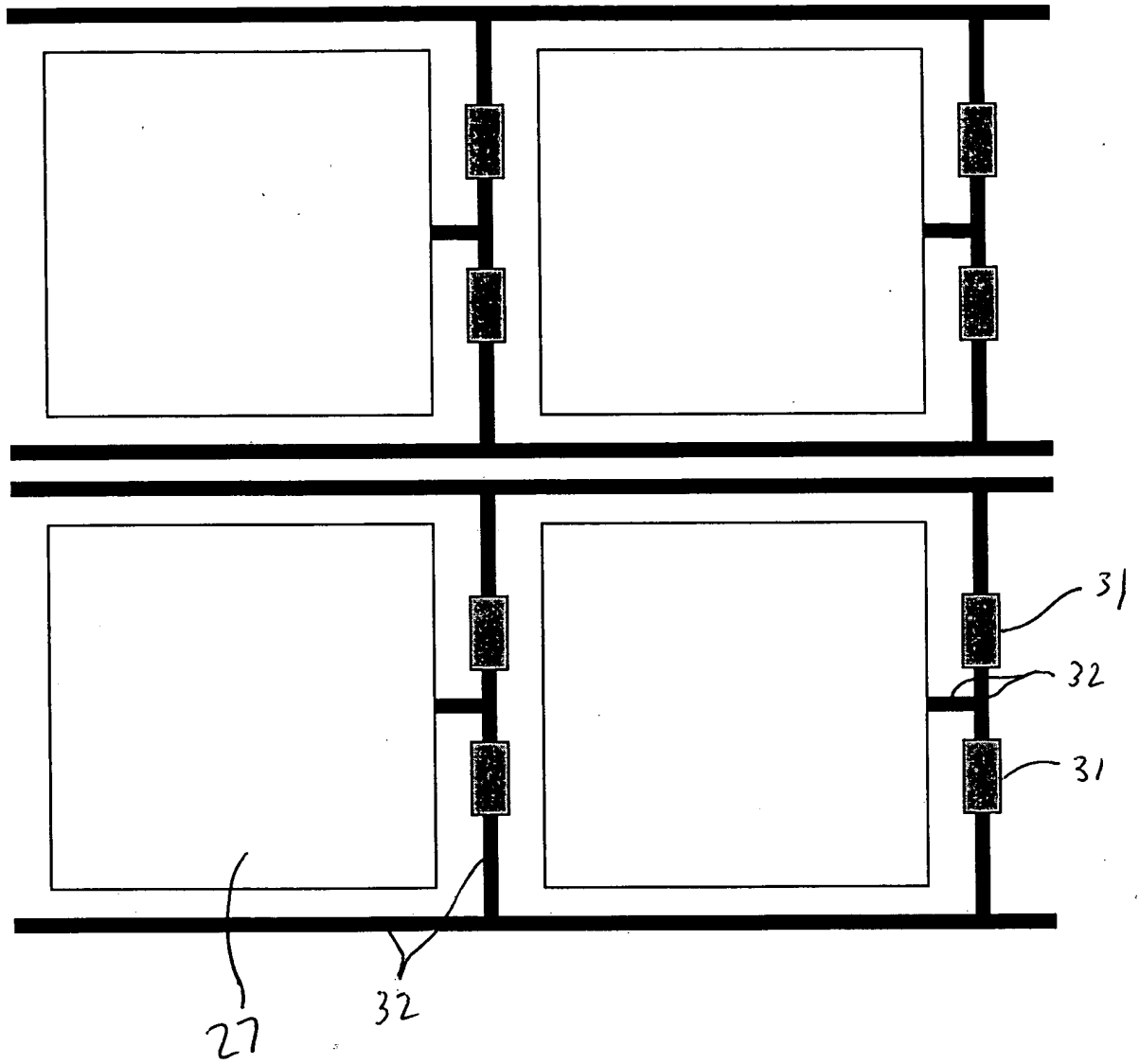


Fig. 7C

60 ↘

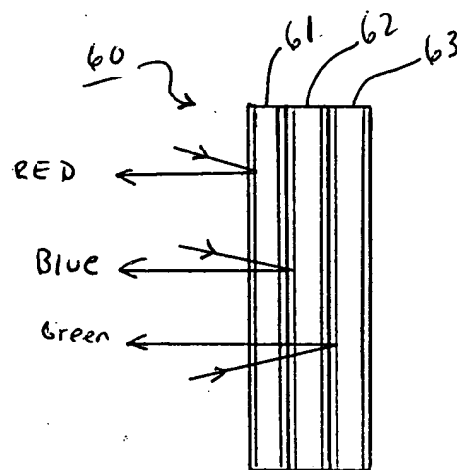
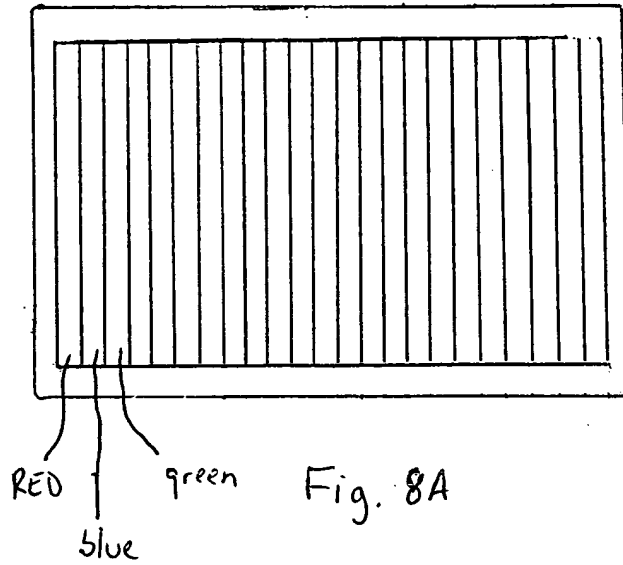


Fig. 8B

60 ↓

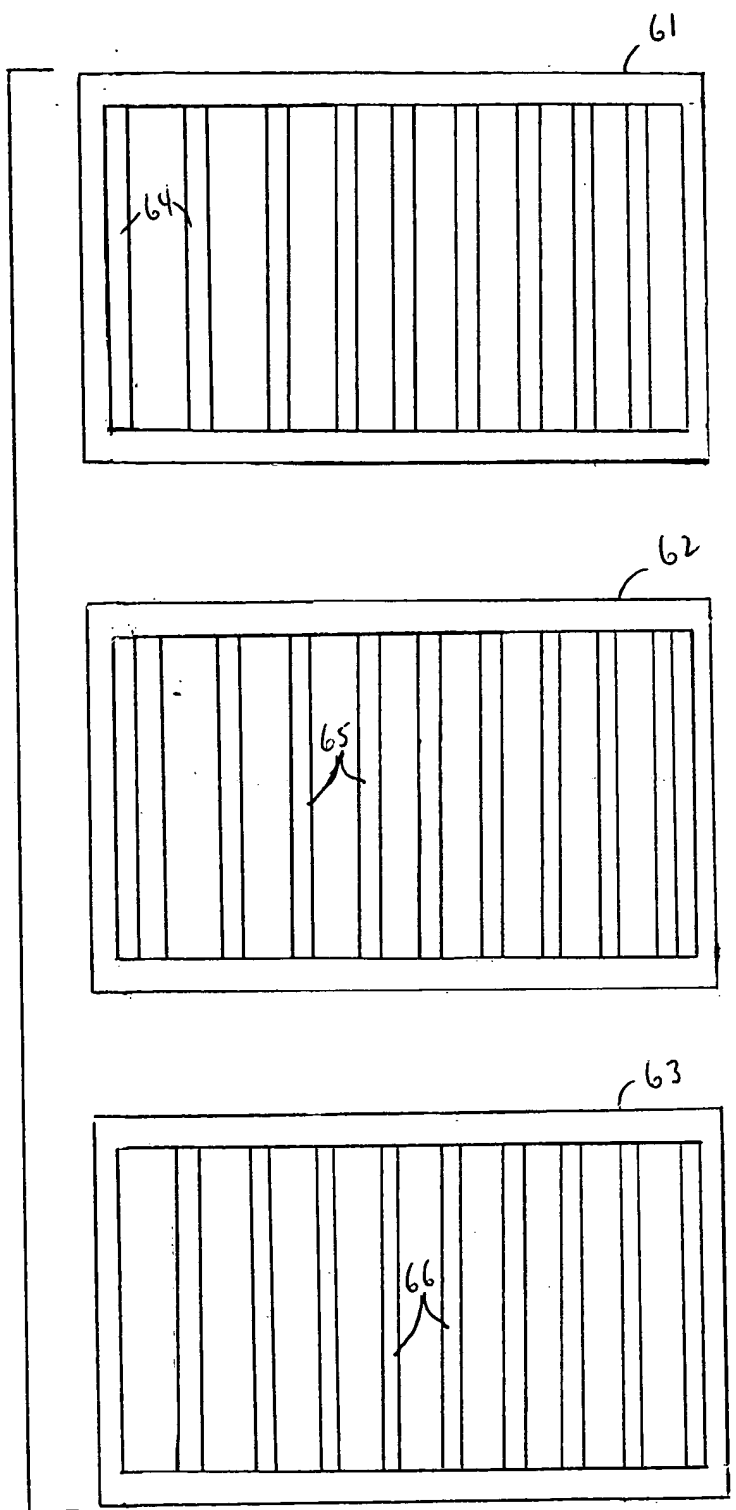


Fig. 8C